ABSTRACT

METHOD FOR TREATING A TRANSPORT SUPPORT FOR THE CONVEYANCE AND ATMOSPHERIC STORAGE OF SEMICONDUCTOR SUBSTRATES, AND TREATMENT STATION FOR THE IMPLEMENTATION OF SUCH A METHOD

The aim of the invention is to provide a method for the treatment of a transport support (1) for the conveyance and storage of semiconductor substrates, with said support (1) possibly having first undergone a cleaning operation using a liquid. The method includes a treatment stage in which the transport support (1) is placed in a sealed chamber (4) connected to a vacuum pump (5) and said transport support (1) is subjected to the combined action of a subatmospheric pressure and infrared radiation to favor the removal of foreign bodies on the walls of the transport support (1).

The invention also concerns a treatment station for a transport support (1) for implementation of the method.

Figure 2